L Number	Hits	Search Text	DB	Time stamp
17	3923	(photosensitive or (resist near4 film$1)) and (mask$4 or pattern$1) and (substrate$1 or workpiece$1) and ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/16 12:54
18	306	((photosensitive or (resist near4 film$1)) and (mask$4 or pattern$1) and (substrate$1 or workpiece$1) and ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1))) and ((photosensitive or (resist near4 film$1)) same (mask$4 or pattern$1) same ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/16 13:01
20	42	(((photosensitive or (resist near4 film$1)) and (mask$4 or pattern$1) and (substrate$1 or workpiece$1) and ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1))) and ((photosensitive or (resist near4 film$1)) same (mask$4 or pattern$1) same ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1)))) and (347/$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/16 13:01
27	25	((((photosensitive or (resist near4 film$1)) and (mask$4 or pattern$1) and (substrate$1 or workpiece$1) and ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1))) and ((photosensitive or (resist near4 film$1)) same (mask$4 or pattern$1) same ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1)))) and (347/$.ccls.)) and align$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/16 13:01
28	13	(((((photosensitive or (resist near4 film$1)) and (mask$4 or pattern$1) and (substrate$1 or workpiece$1) and ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1))) and ((photosensitive or (resist near4 film$1)) same (mask$4 or pattern$1) same ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1)))) and (347/$.ccls.)) and align$4) and mov$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/16 13:03
29	8	((((((photosensitive or (resist near4 film$1)) and (mask$4 or pattern$1) and (substrate$1 or workpiece$1) and ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1))) and ((photosensitive or (resist near4 film$1)) same (mask$4 or pattern$1) same ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1)))) and (347/$.ccls.)) and align$4) and mov$4) and rotat$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/16 13:02

| 30 | 34 | ((((photosensitive or (resist near4 film$1)) and (mask$4 or pattern$1) and (substrate$1 or workpiece$1) and ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1))) and ((photosensitive or (resist near4 film$1)) same (mask$4 or pattern$1) same ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1)))) and (347/$.ccls.)) not ((((((photosensitive or (resist near4 film$1)) and (mask$4 or pattern$1) and (substrate$1 or workpiece$1) and ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1))) and ((photosensitive or (resist near4 film$1)) same (mask$4 or pattern$1) same ((deposit$4 or eject$4) with (ink$1 or liquid$1 or fluid$1)))) and (347/$.ccls.)) and align$4) and mov$4) and rotat$4) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/16 13:03 |